

## Annex 4

### JPO/IPR Training Course for Practitioners Specializing in Trademarks

#### 1. Duration:

October 12 - 30, 2020

[Number of days required for this course (around six hours per day): 10 days]

[Application Deadline: **August 19, 2020**]

#### 2. Objective:

To deepen one's knowledge on intellectual property in general, as well as to deepen one's understanding of and enhance one's professional capabilities on trademark practices, by hearing lectures and holding discussions on the trademark system, trademark examination standards of the Madrid System, and the use of trademark information.

#### 3-1. Specific Requirement(s) for This Course:

Candidates have to be professionals working in one of the following positions:

- 1) Patent/trademark attorneys and IP lawyers in the private sector who are involved in trademark practices; OR
- 2) Employees engaged in trademark practices in the private sector.

**\*Persons working at Japanese enterprises are eligible for this program.**

#### 3-2. General Requirements (applicants must meet all of the following requirements):

Candidates have to:

- (1) be nominated by the IP Office in their countries.
- (2) be engaged in the field of IPR.
- (3) be university graduates and/or have equivalent professional experience.
- (4) be physically and mentally prepared to undergo an intensive training course.
- (5) be persons who are not full-time students or armed forces personnel.
- (6) continue working in the same field after completing the training course.
- (7) be persons who have not participated in any of the JPO/IPR training courses during FY2019 or FY2020, in principle.
- (8) have adequate English language ability to attend lectures and discussions, as well as make reports.
  - \* If English ability is considered to be insufficient, an interview will be conducted by telephone to confirm English proficiency.
- (9) have considerable knowledge of the IPR system, with more than three years of experience in the field of IPR, in principle.
- (10) be under 50 years of age.

\* If nominated candidates do not meet all of the requirements of 3-1 and 3-2 above, the Screening Committee may consider them under certain circumstances. **The special circumstances for their**

**nomination must be listed in the “Comments of recommendation/Reason of the priority” column of the Priority List, and necessary documentation provided if necessary.**

#### **4. Language:**

Lectures, visits and discussions will be carried out in English or in Japanese with English interpretation. The course documents and training materials will be prepared in English.

#### **5. Training Schedule: TBD**

The course schedule below was completed in FY2019 which was held in Japan as an in-person course. It is provided for your reference only. Please note that the FY2020 schedule will be different, and the subject contents may be somewhat different from FY2019 as well.

### (Ref.: FY2019) JPO/IPR Training Course for Practitioners Specializing in Trademarks

**[Japan Time]**  
AM 10:00 - 13:00  
PM 14:00 - 17:00

Date		Subject	Venue
Day 1	AM	Welcome Addresses	APIC
		Visit to INPIT Visit to the Trial Court	JPO
		APIC Orientation	APIC
	PM	Trademark Strategy in Companies	APIC
Day 2	AM	Practices for Applications of the Madrid Protocol	APIC
	PM		
Day 3	AM	Comparison of Trademark System in Various Countries and Discussion (Includes Unfair Competition Prevention Act Cases)	APIC
	PM		
Day 4	AM	Trademark Application Practices	APIC
	PM		
Day 5	AM	Trademark Searches (Trademark Classifications & Search Exercises)	APIC PC room
	PM		
Day 6	AM	Trademark Examination Standards	APIC
	PM	Case Study (Litigation Rescinding a Trial Decision)	APIC
Day 7	AM	Fieldwork	Company
	PM	The Current Status of Corporate Intellectual Management (Company Visit)	
Day 8	AM	Acquisition of the right of Special Trademark (Non-Traditional Trademark, Three-dimensional Trademark)	APIC
	PM	Trademark Infringement Dispute	APIC
Day 9	AM	Trademark Infringement (Case Studies)	APIC
	PM		
Day 10	AM	Overall Discussion	APIC

	PM	Evaluation Meeting	APIC
		Closing Ceremony	APIC